Nanonex Introduces Innovative Nanoimprint Lithography Manufacturing System to Meet Growing Demand for Mold Duplication.

PRINCETON, NJ, May 31, 2011 – NANONEX CORPORATION, a pioneer and a leading company in nanoimprint solution, today, announced its new nanoimprint lithography (NIL) manufacturing system, the NX-M200B, for duplicating NIL molds for both semiconductor and hard disk drives (HDDs). Featuring unparalleled performance, based on Nanonex’s unique and patented nanoimprint solution and Air Cushion Press (ACP) technology, the NX-M200B offers not only high performance duplication of high quality NIL molds for both semiconductor and HDD applications, but also unprecedented productivity, ease of use, and flexibility.

There are several next generation lithography technologies vying for manufacturing semiconductors at future technology nodes, with NIL becoming recognized as a practical and effective solution for semiconductor applications. Advanced mold replication is a necessary part of enabling NIL technologies to be deployed as an effective semiconductor manufacturing technology, and the NX-M200B provides a perfect solution. With high throughput, sub-10 nm overlay and the proven, unparalleled performance of ACP, the NX-M200B duplicates molds
with high productivity and in fully automated fashion. With integrated Class 1 environmental control, SMIF box loading, and user friendly software control, the NX-M200B will rapidly become the gold standard for NIL mold duplication.

Nanonex NIL technology, with ACP, is widely recognized as the proven and effective NIL technology. With over 60 machines shipped worldwide, Nanonex has the infrastructure, team, intellectual property, and know-how to be a reliable partner. Nanonex is ready to showcase its NIL capabilities at the 2011 EIPBN Conference in Las Vegas, May 31-June 3. To learn more about Nanonex’s innovative solutions, please visit www.nanonex.com.